

## UMF Equipment – UV Mask Aligner

### Suss MA6 Aligner

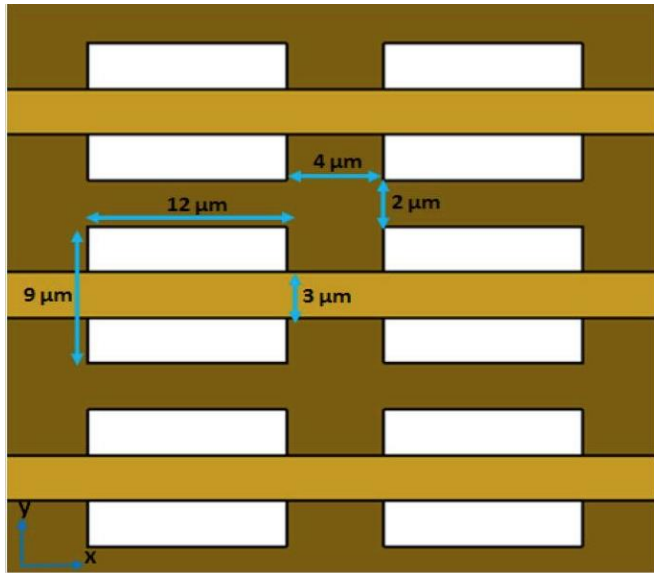
UV mask aligner is used in microfabrication to pattern parts of a thin film or the bulk of a substrate. It uses light to transfer a geometric pattern from a photomask to a light-sensitive chemical "photoresist", or simply "resist," on the substrate. A series of chemical treatments then either engraves the exposure pattern into, or enables deposition of a new material in the desired pattern upon, the material underneath the photoresist.

- Features:
- Light source: 350W UV light
  - Resolution: <math><0.8\mu\text{m}</math> max.
  - Alignment: Top side alignment
  - Alignment accuracy: <math><\pm 0.5\mu\text{m}</math>
  - Substrate: Up to 4" round wafer

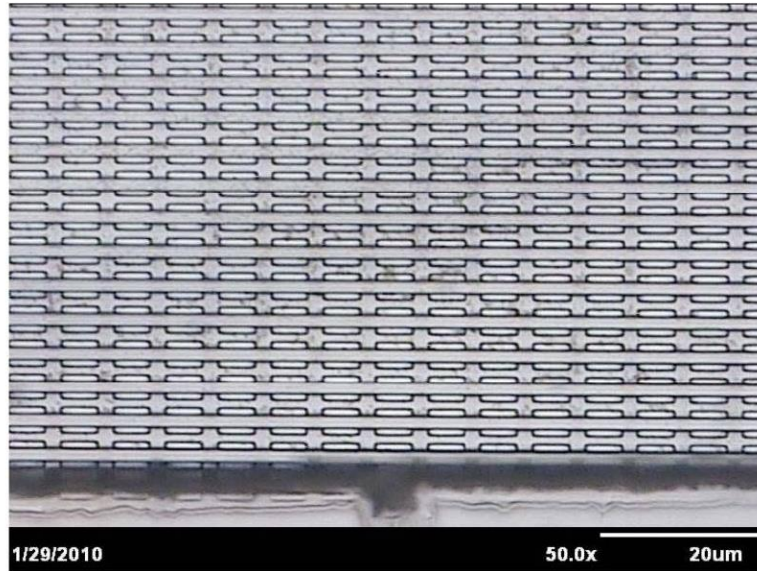
Please refer to supplier information page: <https://www.suss.com/en> for further details of the system.  
For any inquiry, please contact Dr. Terence Wong ([tai-lun.wong@polyu.edu.hk](mailto:tai-lun.wong@polyu.edu.hk)).



UV Mask Aligner



(a)



(b)

(a) Schematic and (b) optical image of a multi-layer polymeric micro-sieve with critical dimensions after photolithography. [*Biomicrofluidics*. 2011 Sep; 5(3): 036504–036504-9]